



Application Serial No. 10/085,759  
File No. NMTI 1002-6 US

RECEIVED

NOV 07 2002

TC 1700

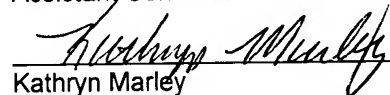
#4  
1756

#4a  
NEAL

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first class mail in an envelope addressed to:

Assistant Commissioner for Patents, Washington, D.C. 20231, on 31 October 2002.

  
Kathryn Marley

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: **Michel Luc Cote et al.**

Examiner: **Unknown**  
Group: **Unknown**

Application No.: **10/085,759**

Filed: **28 February 2002**

Title: **Design and Layout of Phase Shifting  
Photolithographic Masks**

**PRELIMINARY AMENDMENT**

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

Please amend the subject patent application as follows.

**In the Specification:**

Please change page 1, paragraph 4 to read as follows:

*al*  
This application is a continuation-in- part of, and incorporates by reference, the United States Patent Application Serial No. 09/669,359 filed 26 Sep 2000 entitled "Phase Shift Masking for Complex Patterns" having inventor Christophe Pierrat and assigned to the assignee of the present invention, which is related to United States Provisional Patent Application Serial No. 60/215,938 filed 5 Jul 2000 entitled "Phase Shift Masking For Complex Layouts" having inventor Christophe Pierrat and assigned to the assignee of the present invention.